Possible defect stabilization due to simultaneous deuterium exposure during annealing in self-ion damaged W

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Motivation

 Synergistic effects are known to affect defect creation/recovery strong effect on hydrogen isotope retention

 There is a strong need for simultaneous experiments (hydrogen isotope exposure during defect creation/annealing)

 These synergistic effects need to be included in the models in order to accurately predict hydrogen isotope retention and permeation





Studying annealing of heavy-ion damaged W







Effect of D filled defects on annealing



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D presence during annealing clearly different







Next step: study simultaneous annealing+plasma



W-D (no annealing fiducial)

• strong D retention in damaged zone (< 2.2 μm)







Retention diverges for 473 K anneal

- strong D retention in damaged zone (< 2.2 μm)
- D retention change after vacuum anneal or plasma anneal

| | 0 | · | |
|-------|----------------|----------------|--|
| A (K) | W-A-D | W-D-AD-D | |
| 473 | small decrease | small increase | $0.0 \xrightarrow{1}{0} 0.0 \xrightarrow{1}{0} 0.0$ |
| | | | W-D-AD-D 2.0 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 5 |
| | | | |
| | | | depth [μm] |
| TIOO | | | |





PISCES

0.2

- 383 K - 473 K

W-A-D

2.0

[% .

Retention continues to diverge at 573 K

- strong D retention in damaged zone (< 2.2 μ m)
- D retention change after vacuum anneal or plasma anneal

| D retention change after vacuum anneal or plasma anneal | | | |
|---|------------------|-----------------|--|
| A (K) | W-A-D | W-D-AD-D | |
| 473 | small decrease | small increase | |
| 573 | further decrease | slight increase | depth [μm] W-D-AD-D 2.0 |
| | | | - - - - - - - - - - - - - - |
| | | | |
| | | | |
| | | | |





PISCES

0.2 573 K

0.1 pd

0,1 ed 0,1 ed

• 383 K 473 K

W-A-D

depth [µm]

2.0

Retention ~constant up to 673 K plasma anneal

- strong D retention in damaged zone (< 2.2 μm)
- D retention change after vacuum anneal or plasma anneal

| A (K) | W-A-D | W-D-AD-D | |
|-------|------------------|------------------|---------------|
| 473 | small decrease | small increase | |
| 573 | further decrease | slight increase | 2.0 |
| 673 | further decrease | almost no change | |
| | | | L ucentration |





Significant D depopulation and recovery at 773 K

- strong D retention in damaged zone (< 2.2 μm)
- D retention change after vacuum anneal or plasma anneal

| A (K) | W-A-D | W-D-AD-D |
|-------|------------------|----------------------|
| 473 | small decrease | small increase |
| 573 | further decrease | slight increase |
| 673 | further decrease | almost no change |
| 773 | little change | significant decrease |
| | | |



 NRA shows nearly constant D retention in damage zone up to 673 K for plasma anneal
 defect stabilization



W-D (fiducial for comparison)

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- two desorption peaks
 - \circ low-temperature (LT) \Box mono-vacancies/dislocations?
 - o high-temperature (HT) □ vacancy clusters?





Primarily LT grows (beyond damage zone)

- two desorption peaks
 - low-temperature (LT) □ mono-vacancies/dislocations?
 - o high-temperature (HT) □ vacancy clusters?

| A (K) | W-A-D | W-D-AD-D | ption flu |
|-------|---|--|----------------------------------|
| 473 | small decrease of LT no change of HT | strong increase of LT small increase of HT | D desor |
| | | | |
| | | | [^] D/m ² s] |
| | | | ption flux [10 ¹⁷ |
| | 1 | | esor |





LT & HT grow (beyond damage zone)

- two desorption peaks
 - low-temperature (LT) □ mono-vacancies/dislocations?
 - high-temperature (HT) □ vacancy clusters?

| A (K) | W-A-D | W-D-AD-D |
|-------|---|---|
| 473 | small decrease of LT no change of HT | strong increase of LT small increase of HT |
| 573 | strong decrease of both LT & HT | shape changed LT & HT not resolved |
| | | |
| | | |
| | | |





Significant growth of HT (beyond damage zone)

- two desorption peaks
 - low-temperature (LT) □ mono-vacancies/dislocations?
 - o high-temperature (HT) □ vacancy clusters?

| A (K) | W-A-D | W-D-AD-D |
|-------|---|--|
| 473 | small decrease of LT no change of HT | strong increase of LT small increase of HT |
| 573 | strong decrease of both LT & HT | shape changed LT & HT not resolved |
| 673 | further decrease of both LT & HT | decrease of LT strong increase of HT |
| | | |





Significant shift to higher T for HT

- two desorption peaks
 - \circ low-temperature (LT) \Box mono-vacancies/dislocations?
 - high-temperature (HT) □ vacancy clusters?

| A (K) | W-A-D | W-D-AD-D |
|-------|-----------------------|-------------------------|
| | small decrease of LT | strong increase of LT |
| 473 | no change of HT | small increase of HT |
| | strong decrease of | shape changed |
| 573 | both LT & HT | LT & HT not resolved |
| | further decrease of | decrease of LT |
| 673 | both LT & HT | strong increase of HT |
| 773 | little change of both | strong decrease of LT |
| | | HI SNITT and Still high |



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Total D Retention (TDS)

- Initial increase probably due to higher D fluence in the case of W-D-AD-D
- Clearly very different behavior of defect recovery when D is present
- Modeling can give some insight into defect stabilization in the presence of D







Vacuum anneal well fit by 3 traps



- typically 3 trap types used to model TDS spectra
 - LT peak, HT peak, & HT tail







Plasma anneal needs additional trap

- typically 3 trap types used to model TDS spectra
 - LT peak, HT peak, & HT tail
- this work revealed the existence of the 4th trap type (small vacancy clusters?)







Vacuum anneal trap conc. monotonic decrease

- typically 3 trap types used to model TDS spectra
 - LT peak, HT peak, & HT tail
- this work revealed the existence of the 4th trap type (small vacancy clusters?)
- W-A-D
 monotonically decreasing trap densities





Plasma anneal exhibits complex trap evolution

- typically 3 trap types used to model TDS spectra
 - LT peak, HT peak, & HT tail
- this work revealed the existence of the 4th trap type (small vacancy clusters?)
- W-A-D
 monotonically decreasing trap densities
- W-D-AD-D
 complex evolution of trap densities

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Total D retention (including W-D-A-D)







D presence during annealing clearly different

- W-A-D
 - all traps empty during anneal
- W-D-A-D
 - \circ traps partially D filled \square reduced recovery
 - D continuously desorbed while held-at-temperature



• filled = TDS

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D presence during annealing clearly different

- W-A-D
 - all traps empty during anneal
- W-D-A-D
 - traps partially D filled \Box reduced recovery
 - D continuously desorbed while held-at-temperature
- W-D-AD-D
 - traps partially D filled \Box reduced recovery
 - D continuously repopulated with D plasma exposure held-at-temperature
 - mobile defects annihilate at surface/GB but defects migrating further into bulk slowed/stabilized by D?



- open = NRA (damage zone)
- filled = TDS

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Thank you!

- Annealing of W simultaneously exposed to D plasma:
 - obvious synergistic effects
 - reduced defect recovery \Box D induced stabilization of defects
 - Further experimental details
 - M.J. Simmonds et al. 2022 Nucl. Fusion 62 036012
- Future:
 - ending Be work (Be box is gone!) and focusing on synergistic effects in W
 - finalizing plans for heavy ion accelerator (NEC) installation/coupling to PISCES-RF
 - improving modeling capabilities, including synergistic effects in the codes





Experimental Details





Sample Prep



- PCW samples:
 - 1.5 mm thick and 6 mm dia
 - polished and recrystallized





Heavy-ion induced defects



- PCW samples:
 - 1.5 mm thick and 6 mm dia
 - polished and recrystallized
- W self-damaging:
 - 20.3 MeV W⁶⁺ ions at 295 K
 - 7.87 x 10¹⁷ ions/m² □ 0.23 dpa





D decoration of defects







Annealing with or without D plasma







Quantification of D retention





